L Number	Hits	Search Text	DB	Time stamp
1	1	10/666649	USPAT; US-PGPUB	2004/10/27 08:04
3	33	(mask$ near5 (wafer substrate workpiece)) with ((separat$4) with (rota$6))	USPAT; US-PGPUB	2004/10/27 08:09
4	80	(mask$3 near5 (wafer substrate workpiece)) with ((separat$4 remov$5 divid$5) with (rota$6))	USPAT; US-PGPUB	2004/10/27 08:15
5	8	semiconductor with (mask$3 near5 (wafer substrate workpiece)) with ((separat$4 remov$5 divid$5) with (rota$6))	.USPAT; US-PGPUB	2004/10/27 08:21
6	26875	(semiconductor near4 (wafer substrate workpiece)) with (mask$3 photoresist resist)	USPAT; US-PGPUB	2004/10/27 08:23
7	2217	((semiconductor near4 (wafer substrate workpiece)) with (mask$3 photoresist resist)) and ((semiconductor near4 (wafer substrate workpiece)) with (rotat$4 spin$4))	USPAT; US-PGPUB	2004/10/27 08:27
8	1065	(((semiconductor near4 (wafer substrate workpiece)) with (mask$3 photoresist resist)) and ((semiconductor near4 (wafer substrate workpiece)) with (rotat$4 spin$4))) and ((semiconductor near4 (wafer substrate workpiece)) with (separat$4 remov$5 divid$4))	USPAT; US-PGPUB	2004/10/27 08:26
9	479	((((semiconductor near4 (wafer substrate workpiece)) with (mask$3 photoresist resist)) and ((semiconductor near4 (wafer substrate workpiece)) with (rotat$4 spin$4))) and ((semiconductor near4 (wafer substrate workpiece)) with (separat$4 remov$5 divid$4))) and ((mask$3 photoresist resist) with (rotat$4 spin$4))	USPAT; US-PGPUB	2004/10/27 08:29
11	8	((((((semiconductor near4 (wafer substrate workpiece)) with (mask$3 photoresist resist)) and ((semiconductor near4 (wafer substrate workpiece)) with (rotat$4 spin$4))) and ((semiconductor near4 (wafer substrate workpiece)) with (separat$4 remov$5 divid$4))) and ((mask$3 photoresist resist) with (rotat$4 spin$4))) and (serarat$ near$3 device)) and (wedge)	USPAT; US-PGPUB	2004/10/27 08:31
10	450	(((((semiconductor near4 (wafer substrate workpiece)) with (mask$3 photoresist resist)) and ((semiconductor near4 (wafer substrate workpiece)) with (rotat$4 spin$4))) and ((semiconductor near4 (wafer substrate workpiece)) with (separat$4 remov$5 divid$4))) and ((mask$3 photoresist resist) with (rotat$4 spin$4))) and (serarat$ near$3 device)	USPAT; US-PGPUB	2004/10/27 08:44
12	467	(((((semiconductor near4 (wafer substrate workpiece)) with (mask$3 photoresist resist)) and ((semiconductor near4 (wafer substrate workpiece)) with (rotat$4 spin$4))) and ((semiconductor near4 (wafer substrate workpiece)) with (separat$4 remov$5 divid$4))) and ((mask$3 photoresist resist) with (rotat$4 spin$4))) and (separat$ near$3 device)	USPAT; US-PGPUB	2004/10/27 08:47
13	273	((((((semiconductor near4 (wafer substrate workpiece)) with (mask$3 photoresist resist)) and ((semiconductor near4 (wafer substrate workpiece)) with (rotat$4 spin$4))) and ((semiconductor near4 (wafer substrate workpiece)) with (separat$4 remov$5 divid$4))) and ((mask$3 photoresist resist) with (rotat$4 spin$4))) and (separat$ near$3 device)) and rotat$4	USPAT; US-PGPUB	2004/10/27 08:45
14	17	(((((semiconductor near4 (wafer substrate workpiece)) with (mask$3 photoresist resist)) and ((semiconductor near4 (wafer substrate workpiece)) with (rotat$4 spin$4))) and ((semiconductor near4 (wafer substrate workpiece)) with (separat$4 remov$5 divid$4))) and ((mask$3 photoresist resist) with (rotat$4 spin$4))) and (separat$ near device)	USPAT; US-PGPUB	2004/10/27 08:47
15	22	(((((semiconductor near4 (wafer substrate workpiece)) with (mask$3 photoresist resist)) and ((semiconductor near4 (wafer substrate workpiece)) with (rotat$4 spin$4))) and ((semiconductor near4 (wafer substrate workpiece)) with (separat$4 remov$5 divid$4))) and ((mask$3 photoresist resist) with (rotat$4 spin$4))) and (separat$ near device wedge adj shap$3)	USPAT; US-PGPUB	2004/10/27 08:57
16	61	"3691694"	USPAT; US-PGPUB	2004/10/27 08:57

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